

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---|---|---------------------|
| 87 | 45 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:20 |
| 88 | 0 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) not us.pc. | DERWENT | 2003/07/22 15:32 |
| 89 | 0 | (430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not us.pc. | DERWENT | 2003/07/22 15:32 |
| 90 | 26 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:34 |
| 91 | 3048 | 430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:44 |
| 92 | 36 | ((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:39 |
| 93 | 915 | ((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:40 |
| 94 | 18 | resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:40 |
| 95 | 36 | 430/314,323-324.ccls. and (planarization adj layer) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:41 |
| 96 | 11 | (resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:41 |

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| 97 | 1 | ((resist or photoresist) and ((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3))) and ((grey or gray) with mask) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:41 |
| 98 | 2 | (resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 16:18 |
| 99 | 17 | (((slop\$3 or inclin\$3 or taper\$3) with (etch\$3)) and 430/320.ccls.) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))) not (((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)) not (430/314,323-324.ccls. and (planarization adj layer) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:43 |
| - | 830 | (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) and (etch\$3)) and (grey or gray) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/24 16:24 |

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| - | 35 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB DERWENT | 2003/07/22 15:19 |
| - | 0 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)) not us.pc. | | 2003/07/22 15:32 |
| - | 0 | (430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not us.pc. | DERWENT | 2003/07/22 15:32 |
| - | 2920 | 430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/17 17:08 |
| - | 6 | ("5962909") or ("5831266") or ("6130109") or ("6025951") or ("6201243") or ("20020043706").PN. | USPAT; US-PGPUB | 2003/01/17 09:20 |
| - | 35 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/17 15:37 |
| - | 29 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) with (photomask or mask or reticle)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/17 15:37 |
| - | 58 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/17 15:41 |
| - | 23 | ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:33 |
| - | 2919 | 430/314,323-324.ccls. not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:35 |
| - | 623 | (mems or moems or microelectromechanical or micro adj electromechanical).ti.ab. | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/18 11:46 |
| - | 26 | ((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:36 |
| - | 884 | (photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls. | USPAT; US-PGPUB | 2003/01/18 13:38 |
| - | 827 | ((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls. | USPAT; US-PGPUB | 2003/01/18 13:39 |

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|---|------|---|---|---------------------|
| - | 827 | ((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:38 |
| - | 17 | resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3) | USPAT; US-PGPUB | 2003/07/22 15:39 |
| - | 6636 | electroplat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3) | USPAT; US-PGPUB | 2003/01/20 15:35 |
| - | 34 | 430/314,323-324.ccls. and (planarization adj layer) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:40 |
| - | 440 | (resist or photoresist) and (air adj bridge) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/23 17:03 |
| - | 210 | (resist or photoresist) same (air adj bridge) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/23 17:04 |
| - | 10 | (resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:41 |
| - | 1 | ((resist or photoresist) and ((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3))) and ((grey or gray) with mask) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:41 |
| - | 2 | (resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/07/22 15:42 |
| - | 900 | (resist or photoresist) and ((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/01/24 11:20 |

